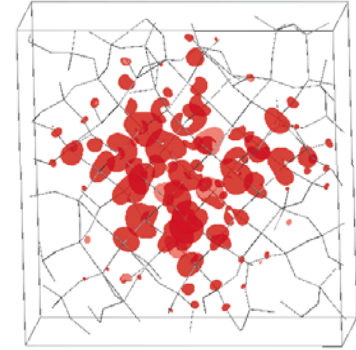
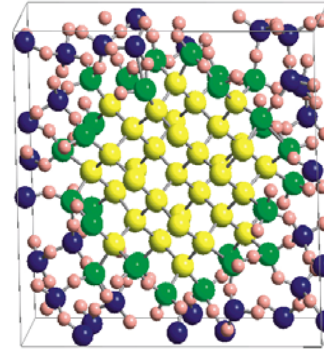


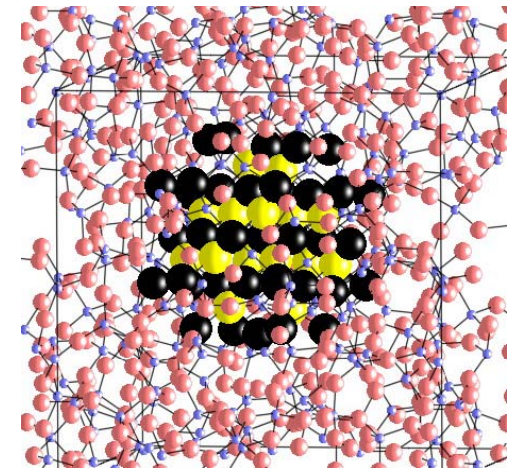
*Si embedded in silica*



# "in-silico" computation of embedded nano-crystals

Computer resources:  
FZ Jülich  
TACC, UT Austin

*Peter Kroll*  
Chemistry & Biochemistry  
UT Arlington, Texas, USA



*SiC embedded in silica*

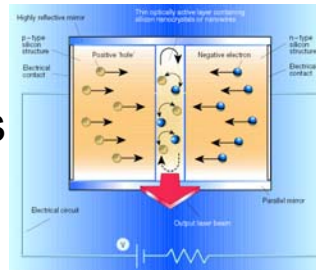
HiPCAT, Arlington, February  
2008

# nanocrystalline Si embedded in a-SiO<sub>2</sub>

- growth of Si-clusters in Si-rich SiO<sub>2</sub>

Nesbit, Appl. Phys. Lett. 1985

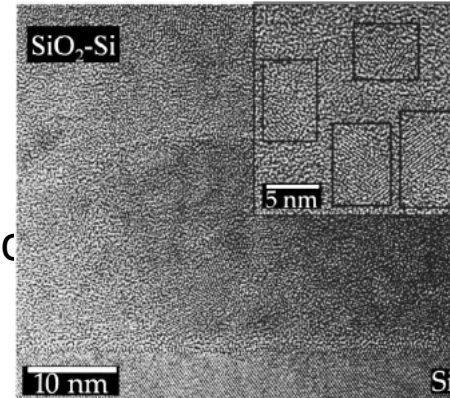
- silicon-based optoelectronics



Pavesi et al., Nature 2000

## Experiments:

- diameter of Si-clusters  $\approx$  2-5 nm
- much unknown about the Si/SiO<sub>2</sub> interface
- trapped states (H, N, O) ?



Torrison et al., J. Appl. Phys. 2002

## ***What causes emission / absorption ? How to improve !***

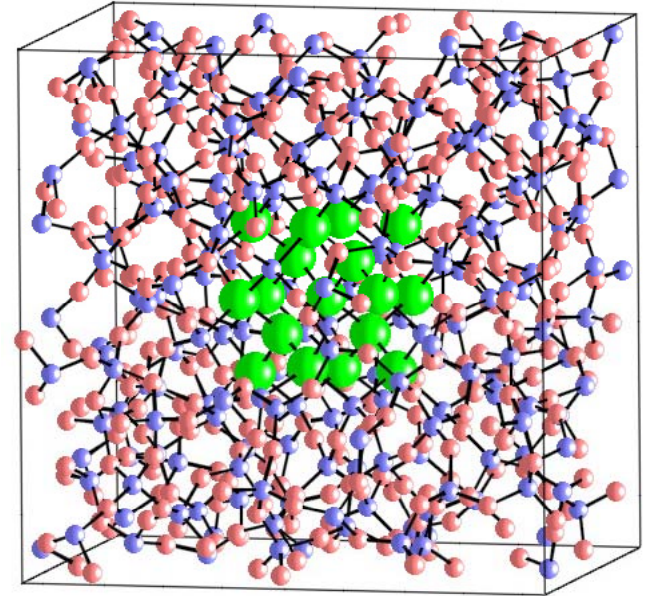
### Goal:

- create realistic models & calculate properties
- develop an understanding of the Si/SiO<sub>2</sub> interface & origin of absorption

# computational approach

## 1. model generation

- 216 Si atoms (3x3x3 conventional unit cell)  
now out of 512 (4x4x4)
- define core atoms = nanocluster, radius  $r$
- for all non-core Si: insert O into Si-Si bonds
  - Si in cristobalite  $\text{SiO}_2$
- randomize the  $\text{SiO}_2$  region, keep core intact  
 $\Rightarrow$  create a glass embedding the nc-Si



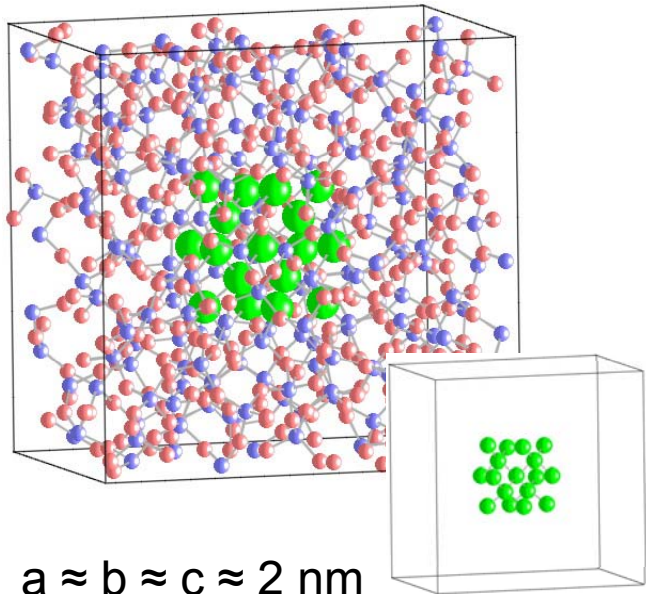
## 2. computation (VASP, LDA/GGA)

models with  $d \approx 0.8 - 1.6$  nm

- structure optimization ( $\sim 300$  cpu·h for 500 atoms,  $\sim 5000$  cpu·h for 1500 atoms)
- energy, density of states, optical properties

# optimized Si@SiO<sub>2</sub> structures

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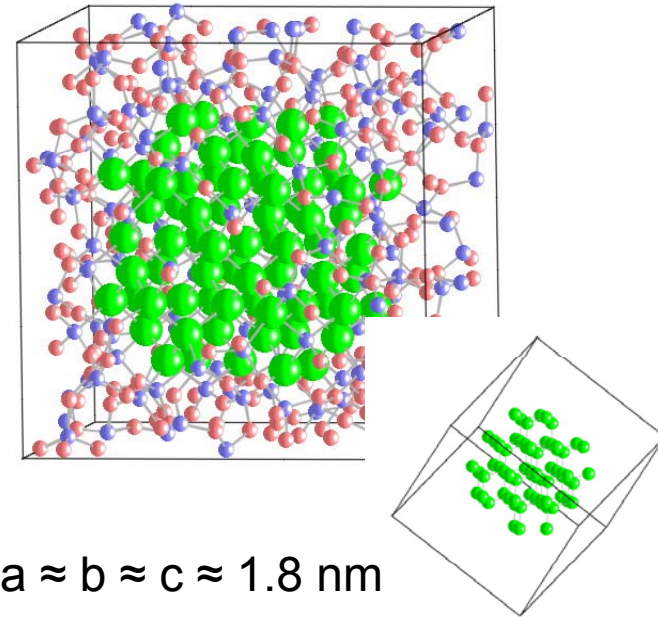
$a \approx b \approx c \approx 2 \text{ nm}$

$d \approx 0.8 \text{ nm}$

596 atoms

26 Si + 190 SiO<sub>2</sub>

Core:  $1+4+12 = 17 \text{ Si}$



$a \approx b \approx c \approx 1.8 \text{ nm}$

$d \approx 1.4 \text{ nm}$

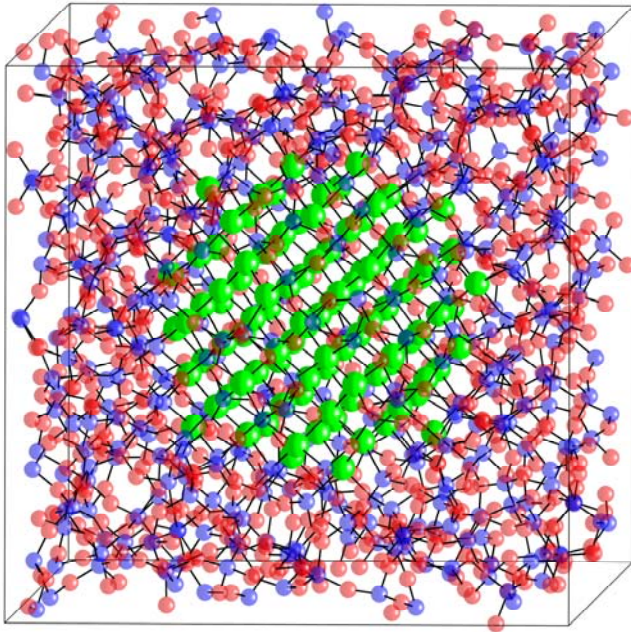
464 atoms

92 Si + 124 SiO<sub>2</sub>

Core:  $1+4+12+12+6+12+24 = 71 \text{ Si}$

# optimized Si@SiO<sub>2</sub> structures & quantum

confi



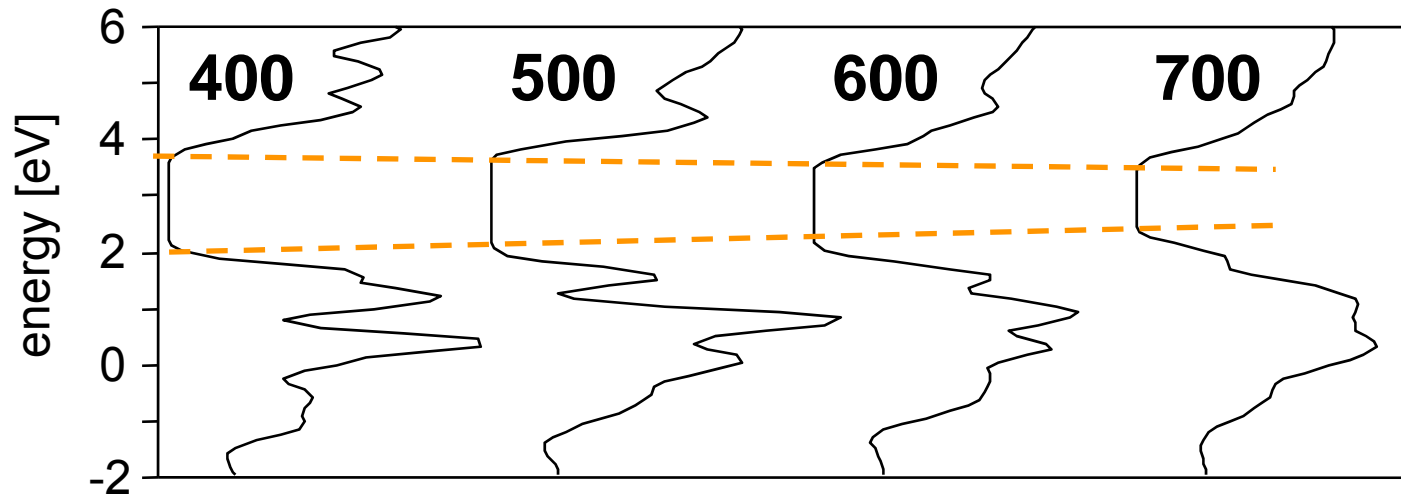
$$a \approx b \approx c \approx 2.6 \text{ nm}$$

$$d \approx 1.6 \text{ nm}$$

1288 atoms

124 Si + 388 SiO<sub>2</sub>

Core:  $1+4+12+12+6+12+24+16+12 = 99$  Si



core-Si projected DOS

$E_{\text{gap}}$  is significantly smaller than for bare or hydrogenated clusters

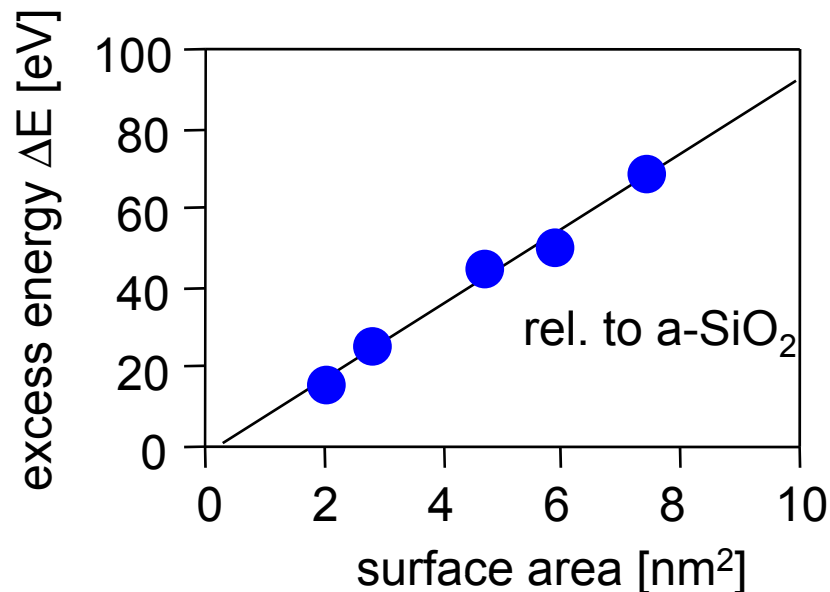
# excess energy of Si@SiO<sub>2</sub>-models / interface

## energy

- targeting interfacial energy/surface tension
- nucleation and growth of nano-crystals
- NO experimental results available for nc-Si

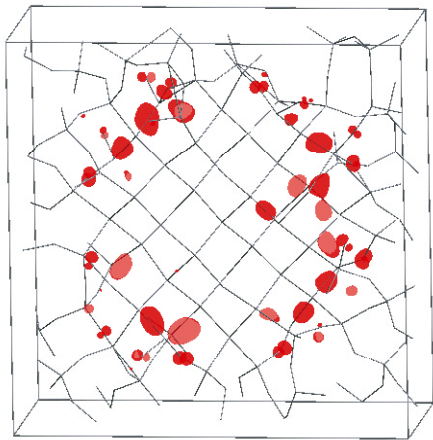
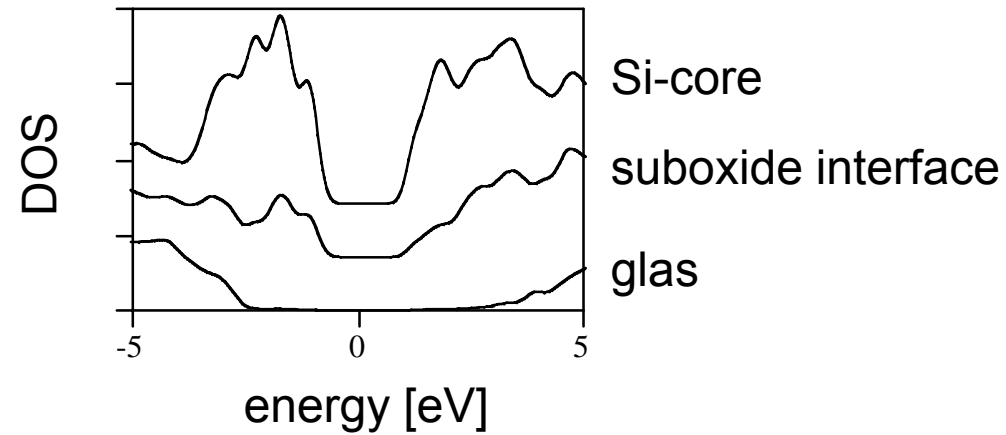
computed energy relative to crystalline Si and amorphous silica

$$\Delta E^{\text{am}} = E(\text{Si@SiO}_2) - [E(\text{c-Si}) + E(\text{a-SiO}_2)]$$

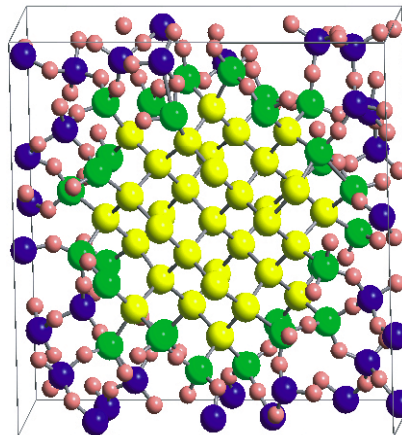


$$\gamma^{\text{am}} = 1.5 \pm 0.3 \text{ J/m}^2$$

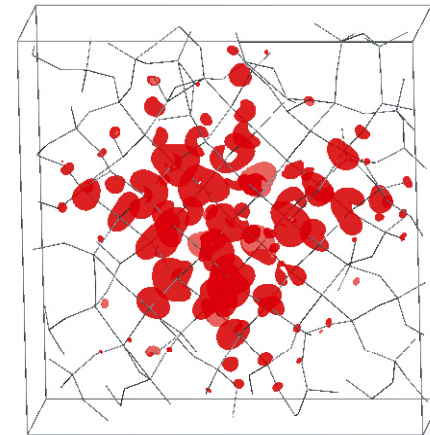
# electronic density of states & spatial distribution of $\rho$



top of valence band (HOMO)



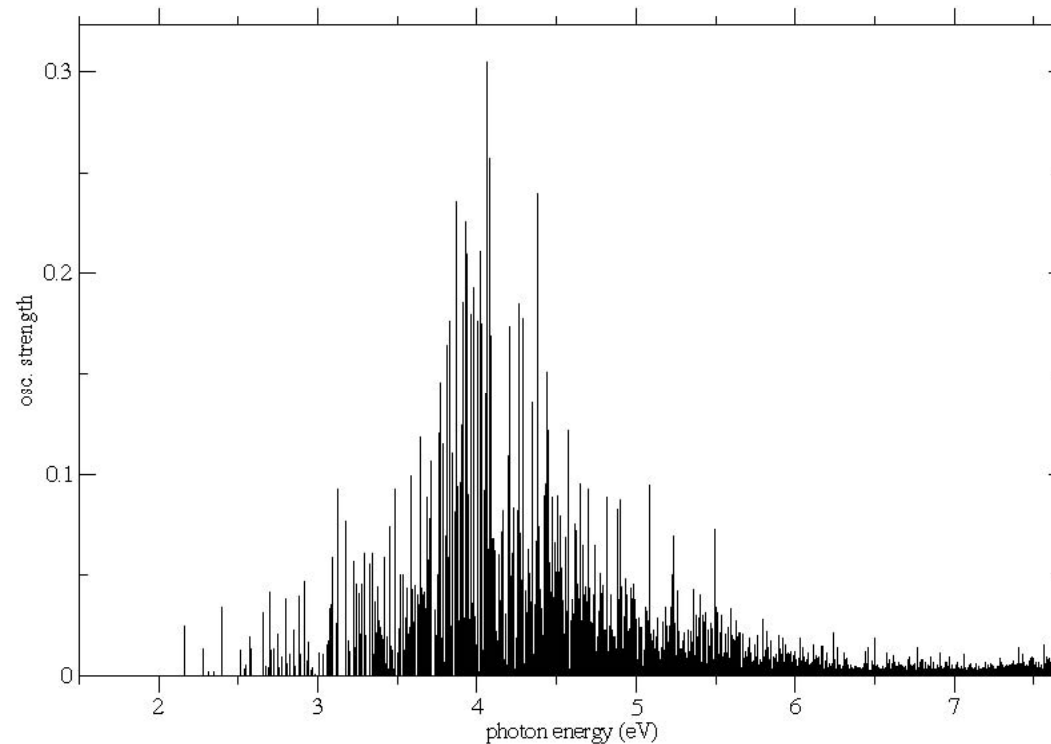
*structure*



bottom of conduction band (LUMO)

- significant differences to free and hydrogenated nc-Si clusters

# oscillator strengths of optical excitations



GW-calculations, treating excited states (L. Ramos, F. Bechstedt, U Jena)

- maximum of absorption at 4 eV (UV-light)

***Can this be tailored to visible light ?***

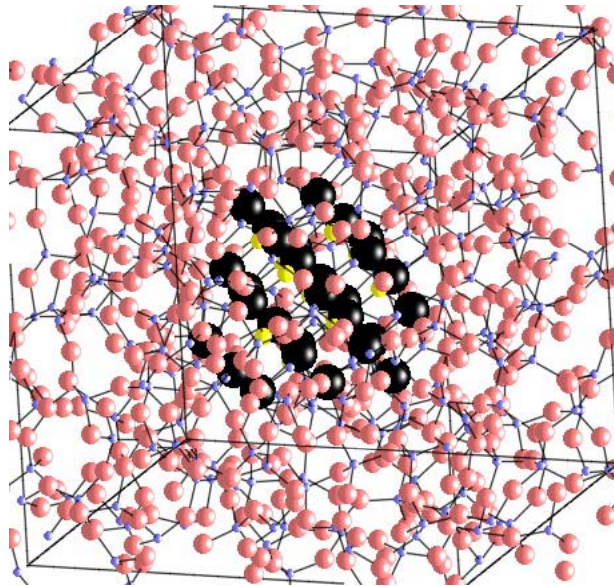


# embedding nc-SiC in a-SiO<sub>2</sub>

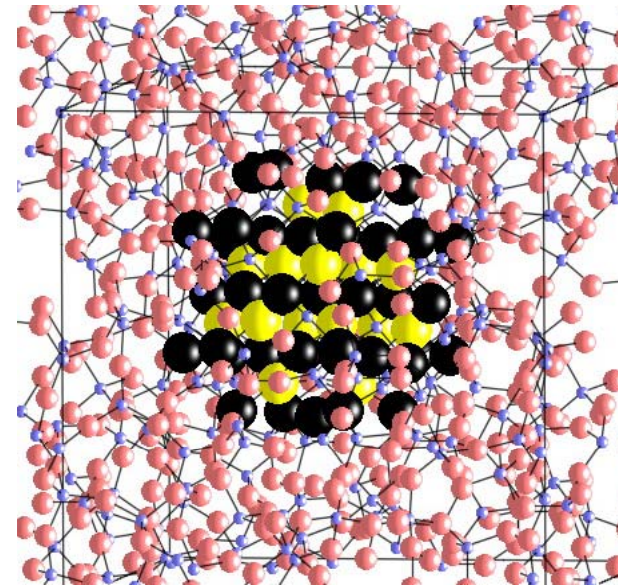
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- model generation analogous to nc-Si @ SiO<sub>2</sub>

$\beta$ -SiC @ a-SiO<sub>2</sub>: Si-termination of SiC-cluster



diameter  $\approx$  1 nm



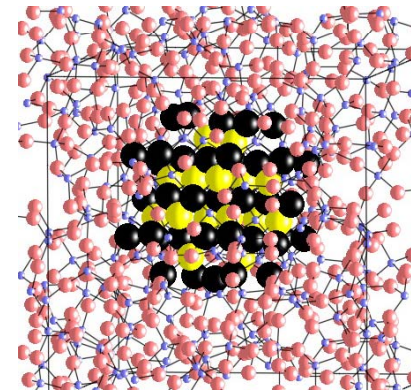
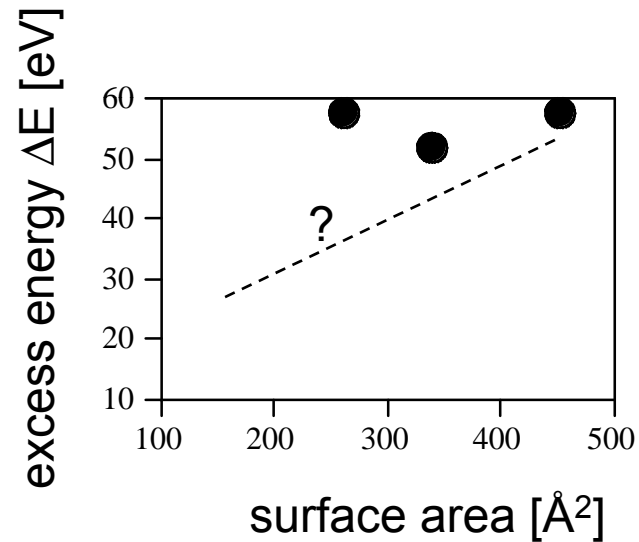
diameter  $\approx$  1.5 nm

# interfacial energy of $\beta$ -SiC @ a-SiO<sub>2</sub>

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- targeting nucleation and growth, NO experimental results available

- reference: a-SiO<sub>2</sub> and  $\beta$ -SiC



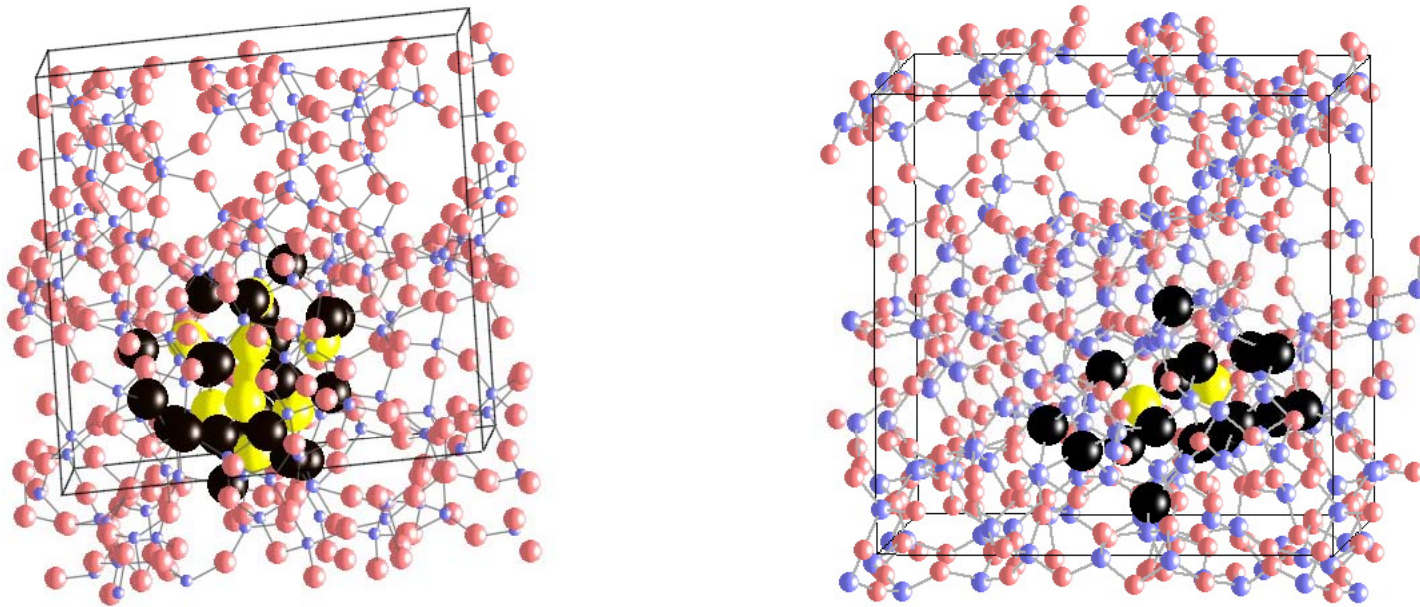
a bit odd !?  
not the expected linear relation

# segregated SiC in SiO<sub>2</sub>

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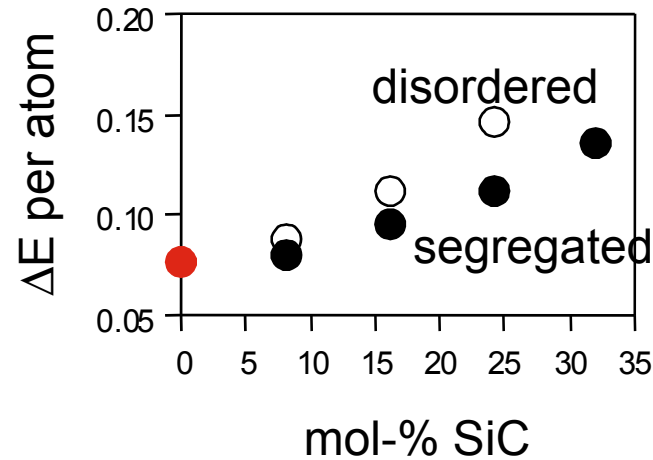
- modelled from random SiCO networks
- through biased construction by increasing the fraction of **SiC<sub>4</sub>** and **SiO<sub>4</sub>**-tetrahedr

⇒ separation of an a-SiC cluster from the ternary phase



this SiC is closer to being 'amorphous'

# energetics of random and segregated a-SiCO

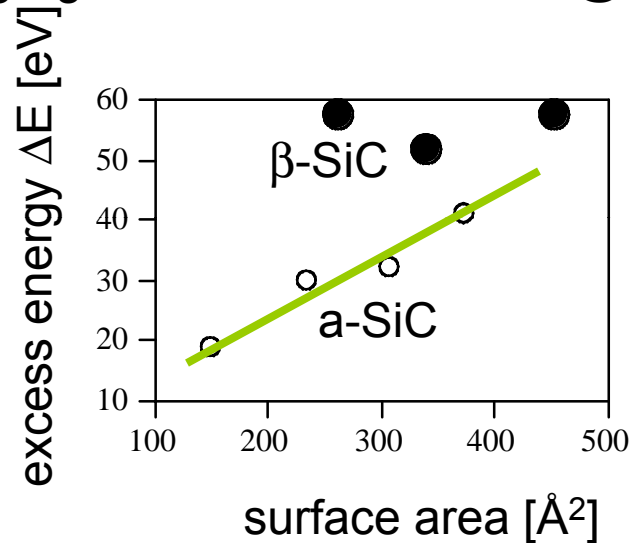


$-T \cdot \Delta S \approx 2-4\%$  of  $\Delta E$

- $\Delta E$  of a-SiO<sub>2</sub> well reproduced
- starting with 25 mol-% SiC, segregation of SiC clearly favored

# surface energy in SiC @ SiO<sub>2</sub>

- cluster models are  $\beta$ -SiC @ SiO<sub>2</sub>
- reference to a-SiO<sub>2</sub> and  $\beta$ -SiC
- segregated models are a-SiC @ SiO<sub>2</sub>



$$\gamma^{\text{am}} \approx 1.6 \pm 0.3 \text{ J/m}^2$$

- trend: "amorphous"-SiC @ a-SiO<sub>2</sub> for small clusters < 3 nm
- $\gamma^{\text{am}}$  comparable to that of nc-Si@SiO<sub>2</sub>

one model  $\beta$ -SiC @ SiO<sub>2</sub> explicitly a) randomized and b) segregated again  
⇒ new optimized structure is lower in energy than initial  $\beta$ -SiC @ SiO<sub>2</sub> !!

# summary

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- "real-size" models of nc-Si and nc-SiC — *in-silico* computation
- embedded clusters can be **very different** in comparison to free clusters
  
- interfacial energy of nc-Si @ SiO<sub>2</sub>
- charge distribution & "spatial" band gap structure
  
- segregation of SiC in a-SiCO comprehensible
- "amorphous"-SiC @ a-SiO<sub>2</sub> favored for small cluster size  $\lesssim 3$  nm

## Outlook

- Fe, Co, Ni @ SiO<sub>2</sub>
- semi-conducting particles embedded in glass SiC, GaN, GaAs
  
- model problem limits: cluster of ~2 nm @ ~2.5 (3) nm of matrix  
⇒ **larger models**
- defects and interface chemistry (N,H)  
⇒ **a manifold of slightly different models**

